

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	2	quantum adj dot adj deposition	USPAT	2002/07/24 08:29
2	BRS	L2	5781	nm near10 width	USPAT	2002/07/24 08:34
3	BRS	L3	58	2 and (electron adj3 beam adj3 pattern)	USPAT	2002/07/24 08:39
4	BRS	L4	41	3 and (ruler or scale or measure or measurement or measuring)	USPAT	2002/07/24 08:42
5	BRS	L5	26	4 and (resist or resists or multilayered or multi-layer or multi-layered)	USPAT	2002/07/24 08:42
6	BRS	L6	8	5 and (organic or molecules or molecule)	USPAT	2002/07/24 08:52
7	BRS	L7	6	6 and (au or ti or cu or si or ag)	USPAT	2002/07/24 08:55
8	BRS	L8	4	7 and (residue or residues or residual or residuals)	USPAT	2002/07/24 08:58
9	BRS	L9	26	(ti near10 au) same (residual or residues or residuals)	USPAT	2002/07/24 09:01
10	BRS	L10	17	(mercaptoalkanoic adj acid) same carboxylic	USPAT	2002/07/24 09:04
11	BRS	L11	348	(deposit or deposited or depositing) near10 (Ti adj8 au)	USPAT	2002/07/24 09:05
12	BRS	L12	124	11 same substrate	USPAT	2002/07/24 09:29
13	BRS	L13	12	12 and ((remove or removing or removed) near5 (multilayer or multilayered or multi-layer or multi-layered or organic))	USPAT	2002/07/24 09:35
14	BRS	L14	16786	(remove or removing or removed) same (multilayer or organic or molecule or resist) same (chemical or electrochemical)	USPAT ; US-PG PUB; EPO; JPO; DERWE NT; IBM_T DB	2002/07/24 09:37
15	BRS	L15	6670	14 and (residues or residual or residue or residuals)	USPAT	2002/07/24 09:38
16	BRS	L16	13	15 and (ti adj5 au)	USPAT	2002/07/24 09:45

	Type	L #	Hits	Search Text	DBs	Time Stamp
17	BRS	L17	0	(remove or removed or removing or lift-off) near5 (organic adj3 molecule adj3 resist)	USPAT	2002/07/24 09:48
18	BRS	L18	379	organic adj resist	USPAT	2002/07/24 09:48
19	BRS	L19	7	molecule adj resist	USPAT	2002/07/24 09:48
20	BRS	L20	8	18 same (removed or removing or removal or remove or removes) same (residual or residue or residues or residuals)	USPAT	2002/07/24 09:52
21	BRS	L21	408	parent adj structure	USPAT	2002/07/24 09:53
22	BRS	L24	10	cu same attached same carboxylic	USPAT	2002/07/24 09:58
23	BRS	L25	86	residual adj structure	USPAT	2002/07/24 10:00
24	BRS	L26	6	25 same (organic or molecule or resist)	USPAT	2002/07/24 10:01
25	BRS	L30	544	e-beam adj lithography	USPAT	2002/07/24 10:04
26	BRS	L31	105	30 and (residual or residue)	USPAT	2002/07/24 10:05
27	BRS	L32	88	31 and (organic or molecule or resist)	USPAT	2002/07/24 10:13
28	BRS	L33	27	molecular same ruler	USPAT	2002/07/24 10:18

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4	BRS	L4	41	3 and (ruler or scale or measure or measurement or measuring)	USPAT	2002/07/24 08:42
5	BRS	L5	26	4 and (resist or resists or multilayered or multi-layer or multi-layered)	USPAT	2002/07/24 08:42
6	BRS	L6	8	5 and (organic or molecules or molecule)	USPAT	2002/07/24 08:52
7	BRS	L7	6	6 and (au or ti or cu or si or ag)	USPAT	2002/07/24 08:55
8	BRS	L8	4	7 and (residue or residues or residual or residuals)	USPAT	2002/07/24 08:58
9	BRS	L9	26	(ti near10 au) same (residual or residues or residuals)	USPAT	2002/07/24 09:01
10	BRS	L10	17	(mercaptoalkanoic adj acid) same carboxylic	USPAT	2002/07/24 09:04
11	BRS	L11	348	(deposit or deposited or depositing) near10 (Ti adj8 au)	USPAT	2002/07/24 09:05
12	BRS	L12	124	11 same substrate	USPAT	2002/07/24 09:29
13	BRS	L13	12	12 and ((remove or removing or removed) near5 (multilayer or multilayered or multi-layer or multi-layered or organic))	USPAT	2002/07/24 09:35
14	BRS	L14	16786	(remove or removing or removed) same (multilayer or organic or molecule or resist) same (chemical or electrochemical)	USPAT ; US-PG PUB; EPO; JPO; DERWE NT; IBM_T DB	2002/07/24 09:37
15	BRS	L15	6670	14 and (residues or residual or residue or residuals)	USPAT	2002/07/24 09:38
16	BRS	L16	13	15 and (ti adj5 au)	USPAT	2002/07/24 09:45

	Type	L #	Hits	Search Text	DBs	Time Stamp
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18	BRS	L18	379	organic adj resist	USPAT	2002/07/24 09:48
19	BRS	L19	7	molecule adj resist	USPAT	2002/07/24 09:48
20	BRS	L20	8	18 same (removed or removing or removal or remove or removes) same (residual or residue or residues or residuals)	USPAT	2002/07/24 09:52
21	BRS	L21	408	parent adj structure	USPAT	2002/07/24 09:53
22	BRS	L24	10	cu same attached same carboxylic	USPAT	2002/07/24 09:58
23	BRS	L25	86	residual adj structure	USPAT	2002/07/24 10:00
24	BRS	L26	6	25 same (organic or molecule or resist)	USPAT	2002/07/24 10:01
25	BRS	L30	544	e-beam adj lithography	USPAT	2002/07/24 10:04
26	BRS	L31	105	30 and (residual or residue)	USPAT	2002/07/24 10:05
27	BRS	L32	88	31 and (organic or molecule or resist)	USPAT	2002/07/24 10:13
28	BRS	L33	27	molecular same ruler	USPAT	2002/07/24 10:18
29	IS&R	L34	52	(438/11).CCLS.	USPAT	2002/07/24 10:46
30	IS&R	L35	652	(438/14).CCLS.	USPAT	2002/07/24 10:52
31	BRS	L36	0	35 and (molecular adj resist)	USPAT	2002/07/24 10:53
32	BRS	L37	2	35 and ruler	USPAT	2002/07/24 10:54
33	BRS	L38	54	35 and (multilayered or multilayer or multi-layered)	USPAT	2002/07/24 11:04
34	IS&R	L39	435	(257/48).CCLS.	USPAT	2002/07/24 11:06
35	BRS	L40	54	39 and (multilayered or multilayer or (multi adj3 layer))	USPAT	2002/07/24 11:07